## IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Application Serial No	
	March 30, 2004
	F. Dan Gealy
Assignee	Micron Technology, Inc
	1792
	Keath T. Cher
	MI22-3685
Title: Method for Reducing Physi	sorption During Atomic Layer Deposition

## RESPONSE TO AUGUST 1, 2008 FINAL OFFICE ACTION

To:

Mail Stop AF

**Commissioner for Patents** 

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